CBCS SCHEME

USN 15NT73

## Seventh Semester B.E. Degree Examination, Dec.2018/Jan.2019 MEMS and NEMS

		MENIS and MENIS	
Time: 3 hrs.		Marks: 80	
Note: Answer any FIVE full questions, choosing one full question from each modul			nodule.
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		Module-1	(08 Marks)
1	a.	Discuss the stepts involved in fabrication of IC's.	(08 Marks)
	b.	Brief about MOEMS and Magnetic MEMS.	(00 1111115)
		OR	
2	a.	Explain in brief about the working principle of Piezo resistive sensors and	piezo ink jet
_		printer.	(08 Marks)
	b.	Write a note on: i) Micro – fluidics ii) RF – MEMS.	(08 Marks)
		Modulo 2	
2		Module-2  Explain the working of capcitive transducer and Bipolar junction transducer.	(08 Marks)
3	a. b.	Write a note on Acoustic Wave transducers.	(08 Marks)
	υ.	Write a note on results wave transports	
		OR	
4	a.	Brief about: i) Quartz Crystal Imbalance ii) Film Bulk Acoustic Wave reson	nator. (08 Marks)
		The state of continuer based transducer	(08 Marks)
	b.	Explain the importance of cantilever based transducer.	(001.201-11)
		Module-3	
5	a.	List and explain the various etching methods.	(08 Marks)
3	b.	With a neat sketch, explain the concept of photolithography.	(08 Marks)
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		OR	
6	a.	Describe the thin film techniques and give the applications.	(08 Marks)
	b.	Define Piezoelectric effect and explain the mechanism with example.	(08 Marks)
		Module-4	(08 Marks)
7	a.	Define packaging and explain the various packaging technologies.	(08 Marks)
	b.	Discuss about the various failure mechanisms.	
	4	OR	
8	a.	Discuss the working of signal amplifiers and signal conditioning.	(08 Marks)
O	b.	Explain the basics of control theory with necessary case studies.	(08 Marks)
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		Module-5	
9	a.	Explain electron beam lithography with sketch.	(08 Marks)
	b.	Explain briefly about future challenges and applications of NEMS.	(08 Marks)

Important Note: 1. On completing your answers, compulsorily draw diagonal cross lines on the remaining blank pages.

2. Any revealing of identification, appeal to evaluator and /or equations written eg, 42+8 = 50, will be treated as malpractice.

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Discuss about Focused ion Beam doping and wet chemical etching. Explain large scale integration of NEMS devices.

OR

(08 Marks)

(08 Marks)